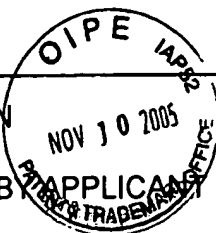


INFORMATION
DISCLOSURE
STATEMENT BY APPLICANT

Sheet 1 of 1



Application Number: 09/638,075
Filing Date: August 11, 2000
First Named Inventor: Hiroji HANAWA, et al.
Group Art Unit: 1753
Examiner Name: Rodney McDonald
Attorney Docket Number: 004609 M Y1

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Examiner's Signature:

Rodney McDonald

Date Considered:

1/6/06

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.